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Kristi L. Davidson  
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4/12/05

Date

**PATENT**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Serial No.: 10/711,649  
Filed: September 29, 2004  
Group Art Unit: 1756  
Examiner: Unknown  
Applicant: Kohei Kawamura, Akira Asano, Koutarou Miyatani, Joseph T. Hillman, Bentley Palmer  
Title: **A METHOD FOR SUPERCRITICAL CARBON DIOXIDE PROCESSING OF FLUORO-CARBON FILMS**  
Attorney Docket: SSIT-114  
Confirmation No.: 5648

Cincinnati, Ohio 45202

April 12, 2005

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**FIRST INFORMATION DISCLOSURE STATEMENT**

In accordance with the duty of candor and good faith imposed by 37 C.F.R. § 1.56 and means of complying therewith according to 37 C.F.R. §§ 1.97 and 1.98, the references listed on the attached Form PTO-1449 are called to the attention of the United States Patent and

Trademark Office in connection with the above-identified patent application. Because the requirement (37 C.F.R. §1.98(a)(2)(i)) for submitting copies of U.S. patents and published applications has been waived, copies of only the other documents are enclosed herewith.

No representation is made that the cited art is the only art or that the cited art represents the best art.

The Examiner is urged to consider all of the cited documents and to make an independent evaluation of the teachings and materiality of each.

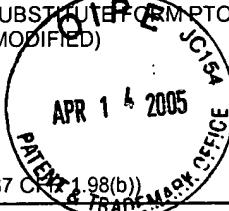
If any additional fees are necessary to complete this communication, please apply them to Deposit Account No. 23-3000.

Respectfully submitted,

WOOD, HERRON & EVANS, L.L.P.

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SUBSTITUTE FORM PTO-1449 (MODIFIED)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE							ATTY. DOCKET NO. SSIT-114		SERIAL NO. 10/711,649	
 (37 CFR 1.98(b))		INFORMATION DISCLOSURE STATEMENT BY APPLICANT  (Use several sheets if necessary)							APPLICANT Kawamura et al.			
									FILING DATE September 29, 2004		GROUP 1756	

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL		PATENT NUMBER							ISSUE DATE	PATENTEE		CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	A.A	2	4	3	9	6	8	9	04/13/1948	Hyde		117	124	06/11/1943
	A.B	2	6	1	7	7	1	9	11/11/1952	C. R. Stewart		23	312	12/29/1950
	A.C	2	6	2	5	8	8	6	01/20/1953	Browne		103	150	08/21/1947
	A.D	3	7	4	4	6	6	0	07/10/1973	Gaines et al.		220	10	12/30/1970
	A.E	3	8	9	0	1	7	6	06/17/1975	Bolon		156	2	12/17/1973
	A.F	3	9	0	0	5	5	1	08/19/1975	Bardoncelli et al.		423	9	03/02/1972
	A.G	3	9	6	8	8	8	5	07/13/1976	Hassan et al.		214	1 BC	08/27/1974
	A.H	4	0	2	9	5	1	7	06/14/1977	Rand		134	11	03/01/1976
	A.I	4	0	9	1	6	4	3	05/30/1978	Zucchini		68	18 C	02/17/1977
	A.J	4	2	1	9	3	3	3	08/26/1980	Harris		8	137	07/03/1978
	A.K	4	2	4	5	1	5	4	01/13/1981	Uehara et al.		250	227	06/28/1978

## FOREIGN PATENTS OR PUBLISHED FOREIGN PATENT APPLICATIONS

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	A.L						
	A.M						
	A.N						
	A.O						
	A.P						
	A.Q						

## OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)

	A.R	J. B. Rubin et al., <u>A Comparison of Chilled DI Water/Ozone and CO<sub>2</sub>-based Supercritical Fluids as Replacements for Photoresist-Stripping Solvents</u> , IEEE/CPMT Int'l Electronics Manufacturing Technology Symposium, pp. 308-314, 1998.
	A.S	<u>Los Alamos National Laboratory</u> , Solid State Technology, pp. S10 & S14, October 1998.
	A.T	<u>Supercritical Carbon Dioxide Resist Remover, SCORR, the Path to Least Photoresistance</u> , Los Alamos National Laboratory, 1998.

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT  (Use several sheets if necessary) (37 CFR 1.98(b))									APPLICANT Kawamura et al.	
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## U.S. PATENT DOCUMENTS

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	B.A	4	3	4	1	5	9	2	07/27/1982	Shortes et al.		156	643	08/04/1975
	B.B	4	3	4	9	4	1	5	09/14/1982	DeFilippi et al.		204	14	08/28/1979
	B.C	4	3	5	5	9	3	7	10/26/1982	Mack et al.		414	217	12/24/1980
	B.D	4	3	6	7	1	4	0	01/04/1983	Wilson		210	110	10/30/1980
	B.E	4	4	0	6	5	9	6	09/27/1983	Budde		417	393	07/27/1981
	B.F	4	4	2	2	6	5	1	12/27/1983	Platts		277	206 R	12/27/1978
	B.G	4	4	7	4	1	9	9	10/02/1984	Blaudszun		134	105	11/09/1982
	B.H	4	4	7	5	9	9	3	10/09/1984	Blander et al.		204	64	08/15/1983
	B.I	4	5	2	2	7	8	8	06/11/1985	Sitek et al.		422	78	03/05/1982
	B.J	4	5	4	9	4	6	7	10/29/1985	Wilden et al.		91	307	08/03/1983
	B.K	4	5	9	2	3	0	6	06/03/1986	Gallego		118	719	11/30/1984

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	B.L						
	B.M						
	B.N						
	B.O						
	B.P						
	B.Q						

## OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)

B.R	Z. Guan et al., <u>Fluorocarbon-Based Heterophase Polymeric Materials. I. Block Copolymer Surfactants for Carbon Dioxide Applications</u> , Macromolecules, Vol. 27, pp 5527-5532, 1994.
B.S	<u>International Journal of Environmentally Conscious Design &amp; Manufacturing</u> , Vol. 2, No. 1, pp. 83, 1993.
B.T	<u>Matson and Smith, Supercritical Fluids</u> , Journal of the American Ceramic Society, Vol. 72, No. 6, pp. 872-874.

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EXAMINER INITIAL		PATENT NUMBER							ISSUE DATE	PATENTEE		CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	C.A	4	6	0	1	1	8	1	07/22/1986	Privat		68	18 C	11/17/1983
	C.B	4	6	2	6	5	0	9	12/02/1986	Lyman		435	287	07/11/1983
	C.C	4	6	7	0	1	2	6	06/02/1987	Messer et al.		204	298	04/28/1986
	C.D	4	6	8	2	9	3	7	07/28/1987	Credle, Jr.		417	393	01/28/1986
	C.E	4	6	9	3	7	7	7	09/15/1987	Hazano et al.		156	345	11/27/1985
	C.F	4	7	4	9	4	4	0	06/07/1988	Blackwood et al.		156	646	05/12/1987
	C.G	4	7	7	8	3	5	6	10/18/1988	Hicks		417	397	08/29/1986
	C.H	4	7	8	8	0	4	3	11/29/1988	Kagiyama et al.		422	292	04/17/1986
	C.I	4	7	8	9	0	7	7	12/06/1988	Noe		220	319	02/24/1988
	C.J	4	8	2	3	9	7	6	04/25/1989	White, III et al.		220	211	05/04/1988
	C.K	4	8	2	5	8	0	8	05/02/1989	Takahashi et al.		118	719	07/08/1987

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	C.L						
	C.M						
	C.N						
	C.O						
	C.P						
	C.Q						

## OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)

	C.R	D. H. Ziger et al., <u>Compressed Fluid Technology: Application to RIE Developed Resists</u> , AIChE Journal, Vol. 33, No. 10, pp. 1585-1591, October 1987.
	C.S	Kirk-Othmer, <u>Alcohol Fuels to Toxicology</u> , Encyclopedia of Chemical Terminology, 3rd ed., Supplement Volume, New York: John Wiley & Sons, pp. 872-893, 1984.
	C.T	Cleaning with Supercritical CO <sub>2</sub> , NASA Tech Briefs, MFS-29611, Marshall Space Flight Center, Alabama, March 1979.

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	D.A	4	8	2	7	8	6	7	05/09/1989	Takei et al.		118	64	11/21/1986
	D.B	4	8	3	8	4	7	6	06/13/1989	Rahn		228	180.1	11/12/1987
	D.C	4	8	6	5	0	6	1	09/12/1989	Fowler et al.		134	108	07/22/1983
	D.D	4	8	7	7	5	3	0	10/31/1989	Moses		210	511	02/29/1988
	D.E	4	8	7	9	0	0	4	11/07/1989	Oesch et al.		203	89	05/04/1988
	D.F	4	8	7	9	4	3	1	11/07/1989	Bertонcini		435	311	03/09/1989
	D.G	4	9	1	7	5	5	6	04/17/1990	Stark et al.		414	217	05/26/1989
	D.H	4	9	2	3	8	2	8	05/08/1990	Gluck et al.		437	225	08/07/1989
	D.I	4	9	2	4	8	9	2	05/15/1990	Kiba et al.		134	123	07/28/1988
	D.J	4	9	2	5	7	9	0	05/15/1990	Blanch et al.		435	52	08/30/1985
	D.K	4	9	3	3	4	0	4	06/12/1990	Beckman et al.		526	207	11/22/1988

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	D.L						
	D.M						
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	D.O						
	D.P						
	D.Q						

## OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)

D.R	N. Basta, <u>Supercritical Fluids: Still Seeking Acceptance</u> , Chemical Engineering Vol. 92, No. 3, pp. 14, February 24, 1985.
D.S	D. Takahashi, <u>Los Alamos Lab Finds Way to Cut Chip Toxic Waste</u> , Wall Street Journal, June 22, 1998.
D.T	<u>Supercritical CO<sub>2</sub> Process Offers Less Mess from Semiconductor Plants</u> , Chemical Engineering Magazine, pp. 27 & 29, July 1988.

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	E.A	4	9	4	4	8	3	7	07/31/1990	Nishikawa et al.		156	646	02/28/1989
	E.B	4	9	5	1	6	0	1	08/28/1990	Maydan et al.		118	719	06/23/1989
	E.C	4	9	6	0	1	4	0	10/02/1990	Ishijima et al.		134	31	11/27/1985
	E.D	4	9	8	3	2	2	3	01/08/1991	Gessner		134	25.4	10/24/1989
	E.E	5	0	1	1	5	4	2	04/30/1991	Weil		134	38	07/21/1988
	E.F	5	0	1	3	3	6	6	05/07/1991	Jackson et al.		134	1	12/07/1988
	E.G	5	0	4	4	8	7	1	09/03/1991	Davis et al.		414	786	01/13/1988
	E.H	5	0	6	2	7	7	0	11/05/1991	Story et al.		417	46	08/11/1989
	E.I	5	0	6	8	0	4	0	11/26/1991	Jackson		210	748	04/03/1989
	E.J	5	0	7	1	4	8	5	12/10/1991	Matthews et al.		134	2	09/11/1990
	E.K	5	1	0	5	5	5	6	04/21/1992	Kurokawa et al.		34	12	08/09/1988

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	E.L						
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	E.N						
	E.O						
	E.P						
	E.Q						

## OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)

	E.R	Y. P. Sun, <u>Preparation of Polymer Protected Semiconductor Nanoparticles Through the Rapid Expansion of Supercritical Fluid Solution</u> , Chemical Physics Letters, pp. 585-588, May 22, 1998.
	E.S	K. Jackson et al., <u>Surfactants and Micromulsions in Supercritical Fluids</u> , Supercritical Fluid Cleaning, Noyes Publications, Westwood, NJ, pp. 87-120, Spring 1998.
	E.T	M. Kryszewski, <u>Production of Metal and Semiconductor Nanoparticles in Polymer Systems</u> , Polimery, pp. 65-73, February 1998.

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	F.A	5	1	4	3	1	0	3	Basso et al.		134	98.1	01/04/1991
	F.B	5	1	5	8	7	0	4	Fulton et al.		252	309	07/25/1990
	F.C	5	1	6	7	7	1	6	Boitnott et al.		118	719	09/28/1990
	F.D	5	1	6	9	2	9	6	Wilden		417	395	03/10/1989
	F.E	5	1	6	9	4	0	8	Biggerstaff et al.		29	25.01	01/26/1990
	F.F	5	1	7	4	9	1	7	Monzyk		252	60	07/19/1991
	F.G	5	1	8	5	0	5	8	Cathey, Jr.		156	656	01/29/1991
	F.H	5	1	8	5	2	9	6	Morita et al.		437	229	04/24/1991
	F.I	5	1	8	6	5	9	4	Toshima et al.		414	217	04/19/1990
	F.J	5	1	8	6	7	1	8	Tepman et al.		29	25.01	04/15/1991
	F.K	5	1	8	8	5	1	5	Horn		417	63	06/03/1991

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	F.L						
	F.M						
	F.N						
	F.O						
	F.P						
	F.Q						

## OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)

	F.R	G. L. Bakker et al., <u>Surface Cleaning and Carbonaceous Film Removal Using High Pressure, High Temperature Water, and Water/CO<sub>2</sub> Mixtures</u> , J Electrochem Soc., Vol. 145, No. 1, pp. 284-291, January 1998.
	F.S	C. K. Ober et al., <u>Imaging Polymers with Supercritical Carbon Dioxide</u> , Advanced Materials, Vol. 9, No. 13, pp. 1039-1043, November 3, 1997.
	F.T	E. M. Russick et al., <u>Supercritical Carbon Dioxide Extraction of Solvent from Micro-Machined Structures</u> , Supercritical Fluids Extraction and Pollution Prevention, ACS Symposium Series, Vol. 670, pp. 255-269, October 21, 1997.

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	G.A	5	1	9	0	3	7	3	03/02/1993	Dickson et al.		366	146	12/24/1991
	G.B	5	1	9	1	9	9	3	03/09/1993	Wanger et al.		220	333	02/24/1992
	G.C	5	1	9	3	5	6	0	03/16/1993	Tanaka et al.		134	56 R	06/24/1991
	G.D	5	1	9	5	8	7	8	03/23/1993	Sahiavo et al.		417	393	05/20/1991
	G.E	5	1	9	6	1	3	4	03/23/1993	Jackson		252	103	08/17/1992
	G.F	5	2	0	1	9	6	0	04/13/1993	Starov		134	11	02/26/1992
	G.G	5	2	1	3	4	8	5	05/25/1993	Wilden		417	393	11/19/1991
	G.H	5	2	1	3	6	1	9	05/25/1993	Jackson et al.		134	1	11/30/1989
	G.I	5	2	1	5	5	9	2	06/01/1993	Jackson		134	1	01/22/1991
	G.J	5	2	1	7	0	4	3	06/08/1993	Novakovi		137	460	02/24/1992
	G.K	5	2	2	1	0	1	9	06/22/1993	Pechacek et al.		220	315	11/07/1991

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	G.L						
	G.M						
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	G.O						
	G.P						
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## OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)

	G.R	N. Dahmen et al., <u>Supercritical Fluid Extraction of Grinding and Metal Cutting Waste Contaminated with Oils</u> , Supercritical Fluids - Extraction and Pollution Prevention, ACS Symposium Series, Vol. 670, pp. 270-279, October 21, 1997.
	G.S	C. M. Wai, <u>Supercritical Fluid Extraction: Metals as Complexes</u> , Journal of Chromatography A, Vol. 785, pp. 369-383, October 17, 1997.
	G.T	C. Xu et al., <u>Submicron-Sized Spherical Yttrium Oxide Based Phosphors Prepared by Supercritical CO<sub>2</sub>-Assisted Nerosolization and Pyrolysis</u> , Appl. Phys. Lett., Vol. 71, No. 22, pp. 1643-1645, September 22, 1997.

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	H.A	5	2	2	2	8	7	6	06/29/1993	Budde		417	393	09/30/1991
	H.B	5	2	2	4	5	0	4	07/06/1993	Thompson et al.		134	155	07/30/1992
	H.C	5	2	2	5	1	7	3	07/06/1993	Wai		423	2	10/25/1991
	H.D	5	2	3	6	6	0	2	08/17/1996	Jackson		210	748	01/28/1991
	H.E	5	2	3	6	6	6	9	08/17/1993	Simmons et al.		422	113	05/08/1992
	H.F	5	2	3	7	8	2	4	08/24/1993	Pawliszyn		62	51.1	02/16/1990
	H.G	5	2	3	8	6	7	1	08/24/1993	Matson et al.		423	397	11/22/1988
	H.H	5	2	4	0	3	9	0	08/31/1993	Kvinge et al.		417	393	03/27/1992
	H.I	5	2	4	3	8	2	1	09/14/1993	Schuck et al.		62	50.6	06/24/1991
	H.J	5	2	4	6	5	0	0	09/21/1993	Samata et al.		118	719	09/01/1992
	H.K	5	2	5	0	0	7	8	10/05/1993	Saus et al.		8	475	05/12/1992

## FOREIGN PATENTS OR PUBLISHED FOREIGN PATENT APPLICATIONS

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## OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)

H.R	Y. Tomioka et al., <u>Decomposition of Tetramethylammonium (TMA) in a Positive Photo-resist Developer by Supercritical Water</u> , Abstracts of Papers 214th ACS Natl Meeting, American Chemical Society, Abstract No. 108, September 7, 1997.
H.S	H. Klein et al., <u>Cyclic Organic Carbonates Serve as Solvents and Reactive Diluents</u> , Coatings World, pp. 38-40, May 1997.
H.T	J. Bühler et al., <u>Linear Array of Complementary Metal Oxide Semiconductor Double-Pass Metal Micro-mirrors</u> , Opt. Eng. Vol. 36, No. 5, pp. 1391-1398, May 1997.

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## U.S. PATENT DOCUMENTS

EXAMINER INITIAL		PATENT NUMBER						ISSUE DATE	PATENTEE		CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	I.A	5	2	5	1	7	7	6	Morgan, Jr. et al.		220	360	08/12/1991
	I.B	5	2	6	1	9	6	5	Moslehi		134	1	08/28/1992
	I.C	5	2	6	6	2	0	5	Fulton et al.		210	639	07/01/1992
	I.D	5	2	6	7	4	5	5	Deweese et al.		68	5 C	07/13/1992
	I.E	5	2	6	9	8	1	5	Schlenker et al.		8	475	11/13/1992
	I.F	5	2	6	9	8	5	0	Jackson		134	2	08/27/1990
	I.G	5	2	7	4	1	2	9	Natale et al.		549	349	06/12/1991
	I.H	5	2	8	0	6	9	3	Heudecker		53	306	10/07/1992
	I.I	5	2	8	5	3	5	2	Pastore et al.		361	707	07/15/1992
	I.J	5	2	8	8	3	3	3	Tanaka et al.		134	31	07/29/1992
	I.K	5	2	9	0	3	6	1	Hayashida et al.		134	2	01/23/1992

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	I.L						
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	I.P						
	I.Q						

## OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)

	I.R	M. H. Jo et al., <u>Evaluation of SiO<sub>x</sub> Aerogel Thin Film with Ultra Low Dielectric Constant as an Intermetal Dielectric</u> , <u>Micrelectronic Engineering</u> , Vol. 33, pp. 343-348, January 1997.
	I.S	J. B. McClain et al., <u>Design of Nonionic Surfactants for Supercritical Carbon Dioxide</u> , <u>Science</u> , Vol. 274, pp. 2049-2052, December 20, 1996.
	I.T	L. Znaidi et al., <u>Batch and Semi-Continuous Synthesis of Magnesium Oxide Powders from Hydrolysis and Supercritical Treatment of Mg(OCH<sub>3</sub>)<sub>2</sub></u> , <u>Materials Research Bulletin</u> , Vol. 31, No. 12, pp. 1527-1535, December 1996.

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	J.A	5	2	9	4	2	6	1	03/15/1994	McDermott et al.		134	7	11/02/1992
	J.B	5	2	9	8	0	3	2	03/29/1994	Schlenker et al.		8	475	08/08/1992
	J.C	5	3	0	4	5	1	5	04/19/1994	Morita et al.		437	231	08/07/1992
	J.D	5	3	0	6	3	5	0	04/26/1994	Hoy et al.		134	22.14	04/27/1992
	J.E	5	3	1	2	8	8	2	05/17/1994	DeSimone et al.		526	201	07/30/1993
	J.F	5	3	1	3	9	6	5	05/24/1994	Palen		134	61	06/01/1992
	J.G	5	3	1	4	5	7	4	05/24/1994	Takahashi		156	646	06/25/1993
	J.H	5	3	1	6	5	9	1	05/31/1994	Chao et al.		134	34	08/10/1992
	J.I	5	3	2	0	7	4	2	06/14/1994	Fletcher et al.		208	89	10/19/1992
	J.J	5	3	2	8	7	2	2	07/12/1994	Ghanayem et al.		427	250	11/06/1992
	J.K	5	3	3	4	3	3	2	08/02/1994	Lee		252	548	07/09/1992

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## OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)

J.R	M. E. Tadros, <u>Synthesis of Titanium Dioxide Particles in Supercritical CO<sub>2</sub></u> , J. Supercritical Fluids, Vol. 9, pp. 172-176, September 1996.
J.S	V. G. Courtecuisse et al., <u>Kinetics of the Titanium Isopropoxide Decomposition in Supercritical Isopropyl Alcohol</u> , Ind. Eng. Chem. Res., Vol. 35, No. 8, pp. 2539-2545, August 1996.
J.T	A. Gabor et al., <u>Block and Random Copolymer Resists Designed for 193 nm Lithography and Environmentally Friendly Supercritical CO<sub>2</sub> Development</u> , SPIE, Vol. 2724, pp. 410-417, June 1996.

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EXAMINER INITIAL		PATENT NUMBER							ISSUE DATE	PATENTEE		CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	K.A	5	3	3	4	4	9	3	08/02/1994	Fujita et al.		430	463	09/29/1993
	K.B	5	3	3	7	4	4	6	08/16/1994	Smith et al.		15	21.1	10/27/1992
	K.C	5	3	3	9	8	4	4	08/23/1994	Stanford, Jr. et al.		134	107	09/07/1993
	K.D	5	3	5	2	3	2	7	10/04/1994	Witowski		156	646	07/10/1992
	K.E	5	3	5	5	9	0	1	10/18/1994	Mielnik et al.		134	105	10/27/1992
	K.F	5	3	5	6	5	3	8	10/18/1994	Wai et al.		210	634	10/21/1991
	K.G	5	3	6	4	4	9	7	11/15/1994	Chau et al.		156	645	08/04/1993
	K.H	5	3	6	8	1	7	1	11/29/1994	Jackson		134	147	07/20/1992
	K.I	5	3	7	0	7	4	0	12/06/1994	Chao et al.		134	1	10/01/1993
	K.J	5	3	7	0	7	4	1	12/06/1994	Bergman		134	3	11/18/1992
	K.K	5	3	7	0	7	4	2	12/06/1994	Mitchell et al.		134	10	07/13/1992

## FOREIGN PATENTS OR PUBLISHED FOREIGN PATENT APPLICATIONS

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	K.L						
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## OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)

K.R	G. L. Schimek et al., <u>Supercritical Ammonia Synthesis and Characterization of Four New Alkali Metal Silver Antimony Sulfides...</u> , J. Solid State Chemistry, Vol. 123, pp. 277-284, May 1996.
K.S	P. Gallagher-Wetmore et al., <u>Supercritical Fluid Processing: Opportunities for New Resist Materials and Processes</u> , SPIE, Vol. 2725, pp. 289-299, April 1996.
K.T	K. I. Papathomas et al., <u>Debonding of Photoresists by Organic Solvents</u> , J. Applied Polymer Science, Vol. 59, pp. 2029-2037, March 28, 1996

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	L.A	5	3	7	7	7	0	5	01/03/1995	Smith, Jr. et al.		134	95.3	09/16/1993
	L.B	5	4	0	1	3	2	2	03/28/1995	Marshall		134	13	06/30/1992
	L.C	5	4	0	3	6	2	1	04/04/1995	Jackson et al.		427	255.1	10/01/1993
	L.D	5	4	0	3	6	6	5	04/04/1995	Alley et al.		428	447	06/18/1993
	L.E	5	4	0	4	8	9	4	04/11/1995	Shiraiwa		134	66	05/18/1993
	L.F	5	4	1	2	9	5	8	05/09/1995	Iliff et al.		68	5 C	12/06/1993
	L.G	5	4	1	7	7	6	8	05/23/1995	Smith, Jr. et al.		134	10	12/14/1993
	L.H	5	4	3	3	3	3	4	07/18/1995	Reneau		220	319	09/08/1993
	L.I	5	4	4	7	2	9	4	09/05/1995	Sakata et al.		266	257	01/21/1994
	L.J	5	4	5	6	7	5	9	10/10/1995	Stanford, Jr. et al.		134	1	08/01/1994
	L.K	5	4	7	0	3	9	3	11/28/1995	Fukazawa		134	3	07/08/1994

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	L.L						
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L.R	J. J. Watkins et al., <u>Polymer/Metal Nanocomposite Synthesis in Supercritical CO<sub>2</sub></u> , Chemistry of Materials, Vol. 7, No. 11, pp. 1991-1994, November 1995.
L.S	E. F. Glynna et al., <u>Supercritical Water Oxidation Research and Development Update</u> , Environmental Progress, Vol. 14, No. 3, pp. 182-192, August 1995.
L.T	P. Gallagher-Wetmore et al., <u>Supercritical Fluid Processing: A New Dry Technique for Photoresist Developing</u> , SPIE, Vol. 2438, pp. 694-708, June 1995.

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	M.A	5	4	7	4	8	1	2	12/12/1995	Truckenmuller et al.		427	430.1	03/07/1995
	M.B	5	4	8	2	5	6	4	01/09/1996	Douglas et al.		134	18	06/21/1994
	M.C	5	4	8	6	2	1	2	01/23/1996	Mitchell et al.		8	142	03/15/1995
	M.D	5	4	9	4	5	2	6	02/27/1996	Paranjepe		134	1	05/04/1995
	M.E	5	5	0	0	0	8	1	03/19/1996	Bergman		156	646.1	12/05/1994
	M.F	5	5	0	1	7	6	1	03/26/1996	Evans et al.		156	344	10/18/1994
	M.G	5	5	0	3	1	7	6	04/02/1996	Dummire et al.		137	15	10/25/1994
	M.H	5	5	0	5	2	1	9	04/09/1996	Lansberry et al.		134	105	11/23/1994
	M.I	5	5	0	9	4	3	1	04/23/1996	Smith, Jr. et al.		134	95.1	11/14/1994
	M.J	5	5	1	4	2	2	0	05/07/1996	Wetmore et al.		134	22.18	12/09/1992
	M.K	5	5	2	2	9	3	8	06/04/1996	O'Brien		134	1	08/08/1994

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## OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)

M.R	A. H. Gabor et al., <u>Silicon-Containing Block Copolymer Resist Materials</u> , Microelectronics Technology - Polymers for Advanced Imaging and Packaging, ACS Symposium Series, Vol. 615, pp. 281-298, April 1995.
M.S	P. C. Tsiantas et al., <u>Effect of Molecular Weight Distribution on the Dissolution Properties of Novolac Blends</u> , SPIE, Vol. 2438, pp. 264-271, June 1995.
M.T	R. D. Allen et al., <u>Performance Properties of Near-Monodisperse Novolak Resins</u> , SPIE, Vol. 2438, pp. 250-260, June 1995.

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	N.A	5	5	2	6	8	3	4	06/18/1996	Mielnik et al.		134	105	08/17/1994
	N.B	5	5	3	3	5	3	8	07/09/1996	Marshall		134	104.4	12/01/1994
	N.C	5	5	4	7	7	7	4	08/20/1996	Gimzewski et al.		428	694	09/01/1993
	N.D	5	5	5	0	2	1	1	08/27/1996	DeCrosta et al.		528	489	12/17/1992
	N.E	5	5	7	1	3	3	0	11/05/1996	Kyogoku		118	719	11/12/1993
	N.F	5	5	8	0	8	4	6	12/03/1996	Hayashida et al.		510	175	01/09/1995
	N.G	5	5	8	9	0	8	2	12/31/1996	Lin et al.		216	2	06/07/1995
	N.H	5	5	8	9	1	0	5	12/31/1996	DeSimone et al.		252	351	05/18/1995
	N.I	5	5	8	9	2	2	4	12/31/1996	Tepman et al.		427	248.1	09/22/1994
	N.J	5	6	2	1	9	8	2	04/22/1997	Yamashita et al.		34	203	10/27/1994
	N.K	5	6	2	9	9	1	8	05/13/1997	Ho et al.		369	112	01/20/1995

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	N.P						
	N.Q						

## OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)

N.R	P. T. Wood et al., <u>Synthesis of New Channeled Structures in Supercritical Amines...</u> , Inorg. Chem., Vol. 33, pp. 1556-1558, 1994.
N.S	J. B. Jerome et al., <u>Synthesis of New Low-Dimensional Quaternary Compounds...</u> , Inorg. Chem., Vol. 33, pp. 1733-1734, 1994.
N.T	J. McHardy et al., <u>Progress in Supercritical CO<sub>2</sub> Cleaning</u> , SAMPE Jour, Vol. 29, No. 5, pp. 20-27, September 1993.

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	O.A	5	6	3	2	8	4	7	05/27/1997	Ohno et al.		156	344	04/24/1995
	O.B	5	6	3	5	4	6	3	06/03/1997	Muraoka		510	175	07/19/1995
	O.C	5	6	3	7	1	5	1	06/10/1997	Schulz		134	2	06/27/1994
	O.D	5	6	4	1	8	8	7	06/24/1997	Beckman et al.		546	26.2	06/24/1997
	O.E	5	6	4	4	8	5	5	07/08/1997	McDermott et al.		34	516	04/06/1995
	O.F	5	6	4	9	8	0	9	07/22/1997	Stapelfeldt		417	63	11/29/1995
	O.G	5	6	5	6	0	9	7	08/12/1997	Olesen et al.		134	1	12/21/1994
	O.H	5	6	6	5	5	2	7	09/09/1997	Allen et al.		430	325	02/03/1997
	O.I	5	6	6	9	2	5	1	09/23/1997	Townsend et al.		68	58	07/30/1996
	O.J	5	6	7	2	2	0	4	09/30/1997	Habuka		117	204	04/25/1996
	O.K	5	6	7	6	7	0	5	10/14/1997	Jureller et al.		8	142	03/06/1995

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O.R	R. Purtell et al., <u>Precision Parts Cleaning Using Supercritical Fluids</u> , J. Vac. Sci. Technol. A., Vol. 11, No. 4, pp. 1696-1701, July 1993.
O.S	E. Bok et al., <u>Supercritical Fluids for Single Wafer Cleaning</u> , Solid State Technology, pp. 117-120, June 1992
O.T	T. Adschiri et al., <u>Rapid and Continuous Hydrothermal Crystallization of Metal Oxide Particles in Supercritical Water</u> , J. Am. Ceram. Cos., Vol. 75, No. 4, pp. 1019-1022, 1992.

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	P.A	5	6	7	9	1	6	9	10/21/1997	Gonzales et al.		134	1.3	12/19/1995
	P.B	5	6	7	9	1	7	1	10/21/1997	Saga et al.		134	3	03/06/1996
	P.C	5	6	8	3	4	7	3	11/04/1997	Jureller et al.		8	142	08/20/1996
	P.D	5	6	8	3	9	7	7	11/04/1997	Jureller et al.		510	286	03/06/1995
	P.E	5	6	8	8	8	7	9	11/18/1997	DeSimone		526	89	02/07/1997
	P.F	5	7	0	0	3	7	9	12/23/1997	Biebl		216	2	02/14/1996
	P.G	5	7	0	2	2	2	8	12/30/1997	Tamai et al.		414	744.5	07/17/1996
	P.H	5	7	0	6	3	1	9	01/06/1998	Holtz		376	203	08/12/1996
	P.I	5	7	1	4	2	9	9	02/03/1998	Combes et al.		430	137	11/04/1996
	P.J	5	7	2	5	9	8	7	03/10/1998	Combes et al.		430	137	11/01/1996
	P.K	5	7	2	6	2	1	1	03/10/1998	Hedrick et al.		521	61	03/21/1996

## FOREIGN PATENTS OR PUBLISHED FOREIGN PATENT APPLICATIONS

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	P.L						
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	P.P						
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## OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)

	P.R	B. N. Hansen et al., <u>Supercritical Fluid Transport - Chemical Deposition of Films</u> , Chem. Mater, Vol. 4, No. 4, pp. 749-752, 1992
	P.S	S. H. Page et al., <u>Predictability and Effect of Phase Behavior of CO<sub>2</sub>/Propylene Carbonate in Supercritical Fluid Chromatography</u> , J. Microcol, Vol. 3, No. 4, pp. 355-369, 1991.
	P.T	T. Brokamp et al., <u>Synthese und Kristallstruktur Eines Gemischvalenten Lithium-Tantalnitride Li<sub>x</sub>Ta<sub>3</sub>N<sub>5</sub></u> , J. Alloys and Compounds, Vol. 176, pp. 47-60, 1991.

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT  (Use several sheets if necessary) (37 CFR 1.98(b))									APPLICANT Kawamura et al.			
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## U.S. PATENT DOCUMENTS

EXAMINER INITIAL		PATENT NUMBER							ISSUE DATE	PATENTEE		CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	Q.A	5	7	3	0	8	7	4	03/24/1998	Wai et al.		210	638	06/02/1994
	Q.B	5	7	3	6	4	2	5	04/07/1998	Smith et al.		438	778	11/14/1996
	Q.C	5	7	3	9	2	2	3	04/14/1998	DeSimone		526	89	09/18/1995
	Q.D	5	7	4	6	0	0	8	05/05/1998	Yamashita et al.		34	211	02/24/1997
	Q.E	5	7	6	6	3	6	7	06/16/1998	Smith et al.		134	2	05/14/1996
	Q.F	5	7	6	9	5	8	8	06/23/1998	Toshima et al.		414	217	08/20/1996
	Q.G	5	7	8	3	0	8	2	07/21/1998	DeSimone et al.		210	634	11/03/1995
	Q.H	5	7	9	7	7	1	9	08/25/1998	James et al.		417	46	10/30/1996
	Q.I	5	7	9	8	1	2	6	08/25/1998	Fujikawa et al.		425	78	05/21/1997
	Q.J	5	7	9	8	4	3	8	08/25/1998	Sawan et al.		528	483	09/09/1996
	Q.K	5	8	0	4	6	0	7	09/08/1998	Hedrick et al.		521	64	10/16/1997

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	Q.L						
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	Q.R	B. M. Hybertson et al., <u>Deposition of Palladium Films by a Novel Supercritical Transport Chemical Deposition Process</u> , Mat. Res. Bull., Vol. 26, pp. 1127-1133, 1991.
	Q.S	D. H. Ziger et al., <u>Compressed Fluid Technology: Application to RIE Developed Resists</u> , AIChE Journal, Vol. 33, No. 10, pp. 1585-1591, October 1987.
	Q.T	D. W. Matson et al., <u>Rapid Expansion of Supercritical Fluid Solutions: Solute Formation of Powders, Thin Films, and Fibers</u> , Ind. Eng. Chem. Res., Vol. 26, No. 11, pp. 2298-2306, 1987.

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	R.A	5	8	0	7	6	0	7	09/15/1998	Smith et al.		427	96	11/14/1996
	R.B	5	8	1	7	1	7	8	10/06/1998	Mita et al.		118	666	05/29/1996
	R.C	5	8	4	7	4	4	3	12/08/1998	Cho et al.		257	632	11/14/1996
	R.D	5	8	6	6	0	0	5	02/02/1999	DeSimone et al.		210	634	11/01/1996
	R.E	5	8	6	8	8	5	6	02/09/1999	Douglas et al.		134	2	07/23/1997
	R.F	5	8	6	8	8	6	2	02/09/1999	Douglas et al.		134	26	07/31/1997
	R.G	5	8	7	2	0	6	1	02/16/1999	Lee et al.		438	705	10/27/1997
	R.H	5	8	7	2	2	5	7	02/16/1999	Beckman et al.		546	336	04/01/1997
	R.I	5	8	7	3	9	4	8	02/23/1999	Kim		134	19	06/24/1997
	R.J	5	8	8	1	5	7	7	03/16/1999	Sauer et al.		68	5	09/09/1996
	R.K	5	8	8	2	1	6	5	03/16/1999	Maydan et al.		414	217	09/10/1997

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	R.R	W. K. Tolley et al., <u>Stripping Organics from Metal and Mineral Surfaces Using Supercritical Fluids</u> , Separation Science and Technology, Vol. 22, pp. 1087-1101, 1987.
	R.S	<u>Final Report on the Safety Assessment of Propylene Carbonate</u> , J. American College of Toxicology, Vol. 6, No. 1, pp. 23-51, 1987.
	R.T	<u>Porous Xerogel Films as Ultra-Low Permittivity Dielectrics for ULSI Interconnect Applications</u> , Materials Research Society, pp. 463-469, 1987.

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	S.A	5 8 8 8 0 5 0							03/30/1999	Fitzgerald et al.		417	46	08/25/1998
	S.B	5 8 9 3 7 5 6							04/13/1999	Berman et al.		438	692	08/26/1997
	S.C	5 8 9 6 8 7 0							04/27/1999	Huynh et al.		134	1.3	03/11/1997
	S.D	5 8 9 8 7 2 7							04/27/1999	Fujikawa et al.		373	110	04/28/1997
	S.E	5 9 0 0 1 0 7							05/04/1999	Murphy et al.		156	359	09/11/1996
	S.F	5 9 0 0 3 5 4							05/04/1999	Batchelder		430	395	07/03/1997
	S.G	5 9 0 4 7 3 7							05/18/1999	Preston et al.		8	158	11/26/1997
	S.H	5 9 0 6 8 6 6							05/25/1999	Webb		427	534	02/10/1997
	S.I	5 9 0 8 5 1 0							06/01/1999	McCullough et al.		134	2	10/16/1996
	S.J	5 9 2 8 3 8 9							07/27/1999	Jevtic		29	25.01	10/21/1996
	S.K	5 9 3 2 1 0 0							08/03/1999	Yager et al.		210	634	06/14/1996

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	S.R	Kawakami et al., <u>A Super Low-k(k=1.1) Silica Aerogel Film Using Supercritical Drying Technique</u> , IEEE, pp. 143-145, 2000.
	S.S	R. F. Reidy, <u>Effects of Supercritical Processing on Ultra Low-k Films</u> , Texas Advanced Technology Program, Texas Instruments and the Texas Academy of Mathematics and Science
	S.T	Anthony Muscat, <u>Backend Processing Using Supercritical CO<sub>2</sub></u> , University of Arizona

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	T.A	5	9	3	4	8	5	6	08/10/1999	Asakawa et al.		414	217	04/28/1997
	T.B	5	9	3	4	9	9	1	08/10/1999	Rush		454	187	02/01/1998
	T.C	5	9	4	4	9	9	6	08/31/1999	DeSimone et al.		210	634	05/02/1997
	T.D	5	9	5	5	1	4	0	09/21/1999	Smith et al.		427	96	11/14/1996
	T.E	5	9	6	5	0	2	5	10/12/1999	Wai et al.		210	634	01/21/1998
	T.F	5	9	7	5	4	9	2	11/02/1999	Brenes		251	175	07/14/1997
	T.G	5	9	7	6	2	6	4	11/02/1999	McCullough et al.		134	2	11/30/1998
	T.H	5	9	7	9	3	0	6	11/09/1999	Fujikawa et al.		100	90	03/25/1998
	T.I	5	9	8	0	6	4	8	11/09/1999	Adler		134	34	02/14/1992
	T.J	5	9	8	1	3	9	9	11/09/1999	Kawamura et al.		438	715	02/15/1995
	T.K	5	9	8	9	3	4	2	11/23/1999	Ikede et al.		118	52	01/28/1997

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	T.R	D. Goldfarb et al., <u>Aqueous-based Photoresist Drying Using Supercritical Carbon Dioxide to Prevent Pattern Collapse</u> , J. Vacuum Sci. Tech. B, Vol. 18, No. 6, pp. 3313, 2000.
	T.S	H. Namatsu et al., <u>Supercritical Drying for Water-Rinsed Resist Systems</u> , J. Vacuum Sci. Tech. B, Vol. 18, No. 6, pp. 3308, 2000.
	T.T	N. Sundararajan et al., <u>Supercritical CO<sub>2</sub> Processing for Submicron Imaging of Fluoropolymers</u> , Chem. Mater., Vol. 12, 41, 2000.

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	U.A	5 9 9 2 6 8 0							11/30/1999	Smith		220	812	01/29/1997
	U.B	5 9 9 4 6 9 6							11/30/1999	Tai et al.		250	288	01/27/1998
	U.C	6 0 0 5 2 2 6							12/21/1999	Aschner et al.		219	390	11/24/1997
	U.D	6 0 1 7 8 2 0							01/25/2000	Ting et al.		438	689	07/17/1998
	U.E	6 0 2 1 7 9 1							02/08/2000	Dryer et al.		134	100.1	06/29/1998
	U.F	6 0 2 4 8 0 1							02/15/2000	Wallace et al.		134	1	12/09/1996
	U.G	6 0 2 9 3 7 1							02/29/2000	Kamikawa et al.		34	516	09/16/1998
	U.H	6 0 3 5 8 7 1							03/14/2000	Eui-Yeol		134	61	03/18/1998
	U.I	6 0 3 7 2 7 7							03/14/2000	Masakara et al.		438	787	11/14/1996
	U.J	6 0 5 3 3 4 8							04/25/2000	Morch		220	263	12/31/1997
	U.K	6 0 5 6 0 0 8							05/02/2000	Adams et al.		137	487.5	09/22/1997

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U.R	Hideaki Itakura et al., <u>Multi-Chamber Dry Etching System</u> , Solid State Technology, pp. 209-214, April 1982		
U.S	Joseph L. Fossez, <u>Diaphragm Pumps Eliminate Seal Problems</u> , Plant Engineering, pp. 1-5, February 1, 1996		
U.T	Bob Agnew, <u>WILDEN Air-Operated Diaphragm Pumps</u> , Process & Industrial Training Technologies, Inc., 1996		

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	V.A	6	0	6	3	7	1	4	05/16/2000	Smith et al.	438	778	11/14/1996
	V.B	6	0	6	7	7	2	8	05/30/2000	Farmer et al.	34	470	02/13/1998
	V.C	6	0	7	7	0	5	3	06/20/2000	Fujikawa et al.	417	399	04/10/1998
	V.D	6	0	7	7	3	2	1	06/20/2000	Adachi et al.	29	25.01	11/07/1997
	V.E	6	0	8	2	1	5	0	07/04/2000	Stucker	68	18 R	07/30/1999
	V.F	6	0	8	5	9	3	5	07/11/2000	Malchow et al.	220	813	08/10/1998
	V.G	6	0	9	7	0	1	5	08/01/2000	McCullough et al.	219	686	10/14/1998
	V.H	6	0	9	9	6	1	9	08/08/2000	Lansbarkis et al.	95	118	10/13/1998
	V.I	6	1	0	0	1	9	8	08/08/2000	Grieger et al.	438	692	02/27/1998
	V.J	6	1	1	0	2	3	2	08/29/2000	Chen et al.	29	25.01	10/01/1998
	V.K	6	1	1	4	0	4	4	09/05/2000	Houston et al.	428	447	05/30/1997

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V.R	Nakata, <u>Active Matrix Substrate and Manufacturing Method Thereof</u> , US 2001/0024247 A1, Publication Date 09/27/2001, Filing Date 03/13/2001, U.S. Class 349/43
V.S	Biberger et al., <u>Method of Depositing Metal Film and Metal Deposition Cluster Tool Including Supercritical Drying/Cleaning Module</u> , US 2002/0001929 A1, Publication Date 01/03/2002, Filed 04/24/2001, U.S. Class 438/584.
V.T	DeYoung et al., <u>Methods for Removing Particles from Microelectronic Structures</u> , US 2002/0112746 A1, Publication Date 08/22/2002, Filed 09/13/2001, U.S. Class 134/36

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	W.A	6	1	2	2	5	6	6	09/19/2000	Nguyen et al.		700	218	03/03/1998
	W.B	6	1	2	8	8	3	0	10/10/2000	Bettcher et al.		34	404	05/15/1999
	W.C	6	1	4	0	2	5	2	10/31/2000	Cho et al.		438	781	05/05/1998
	W.D	6	1	4	5	5	1	9	11/14/2000	Konishi et al.		134	95.2	05/15/1997
	W.E	6	1	4	9	8	2	8	11/21/2000	Vaartstra		216	57	05/05/1997
	W.F	6	1	5	9	2	9	5	12/12/2000	Maskara et al.		118	688	04/22/1999
	W.G	6	1	6	4	2	9	7	12/26/2000	Kamikawa		134	61	06/12/1998
	W.H	6	1	7	1	6	4	5	01/09/2001	Smith et al.		427	96	07/15/1998
	W.I	6	1	8	6	7	2	2	02/13/2001	Shirai		414	217	02/24/1998
	W.J	6	2	0	0	9	4	3	03/13/2001	Romack et al.		510	285	05/27/1999
	W.K	6	2	0	3	5	8	2	03/20/2001	Berner et al.		29	25.01	07/15/1996

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W.R	Beam, <u>High Purity CO<sub>2</sub> and BTEX Recovery</u> , US 2002/0117391 A1, Publication Date 08/29/2002, Filed 01/28/2002, U.S. Class 203/81
W.S	Chiou, <u>Method of Rinsing Residual Etching Reactants/Products on a Semiconductor Wafer</u> , US 2002/0142595 A1, Publication Date 10/03/2002, Filed 03/29/2001, U.S. Class 438/689
W.T	Masuda et al., <u>Process and Apparatus for Removing Residues from the Microstructure of an Object</u> , US 2002/0164873 A1, Publication Date 11/07/2002, Filed 02/08/2002, U.S. Class 438/689

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	X.A	6	2	1	6	3	6	4	04/17/2001	Tanaka et al.		34	448	04/14/1999
	X.B	6	2	2	4	7	7	4	05/01/2001	DeSimone et al.		210	634	02/12/1999
	X.C	6	2	2	8	5	6	3	05/08/2001	Starov et al.		430	327	09/17/1999
	X.D	6	2	2	8	8	2	6	05/08/2001	DeYoung et al.		510	291	10/18/1999
	X.E	6	2	3	2	2	3	8	05/15/2001	Chang et al.		438	725	02/08/1999
	X.F	6	2	3	2	4	1	7	05/15/2001	Rhodes et al.		526	171	09/12/1997
	X.G	6	2	3	5	6	3	4	05/22/2001	White et al.		438	680	05/20/1998
	X.H	6	2	3	9	0	3	8	05/29/2001	Wen		438	745	09/09/1996
	X.I	6	2	4	1	8	2	5	06/05/2001	Wytman		118	733	04/16/1999
	X.J	6	2	4	2	1	6	5	06/05/2001	Vaartstra		430	329	08/28/1998
	X.K	6	2	4	4	1	2	1	06/12/2001	Hunter		73	865.9	03/06/1998

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	X.Q						

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X.R	Cotte et al., <u>Process of Removing Residue Material from a Precision Surface</u> , US 2003/0003762 A1, Publication Date 01/02/2003, Filed 06/27/2001, U.S. Class 438/745
X.S	Chang et al., <u>Method of Avoiding Dielectric Layer Deterioration with a Low Dielectric Constant During a Stripping Process</u> , US 2003/0013311 A1, Publication Date 01/16/2003, Filed 07/03/2001, U.S. Class 438/704
X.T	Reid et al., <u>Method for Removing a Sacrificial Material with a Compressed Fluid</u> , US 2003/0047533 A1, Publication Date 03/13/2003, Filed 06/10/2002, U.S. Class 216/24

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT  (Use several sheets if necessary) (37 CFR 1.98(b))									APPLICANT Kawamura et al.			
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EXAMINER INITIAL		PATENT NUMBER							ISSUE DATE	PATENTEE		CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	Y.A	6	2	5	1	2	5	0	06/26/2001	Keigler		205	89	09/03/1999
	Y.B	6	2	5	5	7	3	2	07/03/2001	Yokoyama et al.		257	760	08/03/1999
	Y.C	6	2	7	0	5	3	1	08/07/2001	DeYoung et al.		8	142	08/28/1998
	Y.D	5	2	7	0	9	4	8	08/07/2001	Sato et al.		430	314	06/07/1999
	Y.E	6	2	7	7	7	5	3	08/21/2001	Mullee et al.		438	692	09/28/1999
	Y.F	6	2	8	4	5	5	8	09/04/2001	Sakamoto		438	30	11/25/1998
	Y.G	6	2	8	6	2	3	1	09/11/2001	Bergman et al.		34	410	01/12/2000
	Y.H	6	3	0	5	6	7	7	10/23/2001	Lenz		269	13	03/30/1999
	Y.I	6	3	0	6	5	6	4	10/23/2001	Mullee		430	329	05/27/1998
	Y.J	6	3	1	9	8	5	8	11/20/2001	Lee et al.		438	787	07/11/2000
	Y.K	6	3	3	1	4	8	7	12/18/2001	Koch		438	692	02/27/2001

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	Y.R	Masuda et al., <u>Process and Apparatus for Removing Residues from the Microstructure of an Object</u> , US 2003/0106573 A1, Publication Date 06/12/2003, Filed 02/08/2002, U.S. Class 134/26
	Y.S	Xu et al., <u>Supercritical Fluid Cleaning of Semiconductor Substrates</u> , US 2003/0125225 A1, Publication Date 07/03/2003, Filed 11/25/2002, U.S. Class 510/175
	Y.T	Jackson, <u>Dense Fluid Cleaning Centrifugal Phase Shifting Separation Process and Apparatus</u> , US 2003/0205510 A1, Publication Date 11/06/2003, Filed 03/13/2001, U.S. Class 210/86.

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	Z.A	6	3	3	4	2	6	6	01/01/2002 Moritz et al.		34	337	09/20/2000
	Z.B	6	3	4	4	1	7	4	02/05/2002 Miller et al.		422	98	04/12/1999
	Z.C	6	3	4	4	2	4	3	02/05/2002 McClain et al.		427	388.1	08/02/2001
	Z.D	6	3	5	5	0	7	2	03/12/2002 Racette et al.		8	142	10/15/1999
	Z.E	6	3	5	8	6	7	3	03/19/2002 Namatsu		430	311	09/03/1999
	Z.F	6	3	6	1	6	9	6	03/26/2002 Spiegelman et al.		210	662	01/19/2000
	Z.G	6	3	6	7	4	9	1	04/09/2002 Marshall et al.		134	104.4	09/15/2000
	Z.H	6	3	8	0	1	0	5	04/30/2002 Smith et al.		438	778	06/02/1999
	Z.I	6	3	8	8	3	1	7	05/14/2002 Reese		257	713	09/25/2000
	Z.J	6	3	8	9	6	7	7	05/21/2002 Lenz		29	559	08/30/2001
	Z.K	6	4	1	8	9	5	6	07/16/2002 Bloom		137	14	11/15/2000

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	Z.R	Masuda et al., <u>Process and Composition for Removing Residues from the Microstructure of an Object</u> , US 2003/0217764 A1, Publication Date 11/27/2003, Filed 05/23/2002, U.S. Class 134/26
	Z.S	DeYoung et al., <u>Methods for Transferring Supercritical Fluids in Microelectronic and Other Industrial Processes</u> , US 2004/0020518 A1, Publication Date 02/05/2004, Filed 05/30/2003, U.S. Class 134/30.
	Z.T	Korzenksi et al., <u>Supercritical Carbon Dioxide/Chemical Formulation for Removal of Photoresists</u> , US 2004/0087457 A1, Publication Date 05/06/2004, Filed 10/31/2002, U.S. Class 510/177

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	AA.A	6	4	2	5	9	5	6	Cotte et al.		134	3	01/05/2001
	AA.B	6	4	3	6	8	2	4	Chooi et al.		438	687	07/02/1999
	AA.C	6	4	5	1	5	1	0	Messick et al.		430	311	02/21/2001
	AA.D	6	4	5	4	5	1	9	Toshima et al.		414	805	03/07/1997
	AA.E	6	4	5	4	9	4	5	Weigl et al.		210	634	11/01/2000
	AA.F	6	4	5	4	9	4	5	Weigl et al.		210	634	11/01/2000
	AA.G	6	4	5	8	4	9	4	Song et al.		430	5	04/27/2000
	AA.H	6	4	6	1	9	6	7	Wu et al.		438	705	07/16/2002
	AA.I	6	4	6	4	7	9	0	Sherstinsky et al.		118	715	03/17/2000
	AA.J	6	4	7	2	3	3	4	Ikakura et al.		438	778	04/03/2001
	AA.K	6	4	7	9	4	0	7	Yokoyama et al.		438	788	01/23/2001

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	AA.R	Inoue et al., Method of High Pressure Treatment, US 2004/0103922 A1, Publication Date 06/03/2004, Filed 11/21/2002, U.S. Class 134/26
	AA.S	Schilling, Fluoride in Supercritical Fluid for Photoresist and Residue Removal, US 2004/0112409 A1, Publication Date 06/17/2004, Filed 12/16/2002, U.S. Class 134/26
	AA.T	Schilling, Tetra-Organic Ammonium Fluoride and HF in Supercritical Fluid for Photoresist and Residue Removal, US 2004/0177867 A1, Publication Date 09/16/2004, Filed 05/20/2003, U.S. Class 134/26

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	BB.A	6	5	5	4	5	0	7	04/29/2003	Namatsu		396	611	12/20/2001
	BB.B	6	5	5	8	4	7	5	05/06/2003	Jur et al.		134	21	04/10/2000
	BB.C	6	5	6	1	2	1	3	05/13/2003	Wang et al.		137	263	06/05/2001
	BB.D	6	5	6	1	2	2	0	05/13/2003	McCullough et al.		137	565.12	04/23/2001
	BB.E	6	5	6	1	4	8	1	05/13/2003	Filonczuk		251	129.12	08/13/2001
	BB.F	6	5	6	1	7	6	7	05/13/2003	Berger et al.		417	53	08/01/2001
	BB.G	6	5	6	2	1	4	6	05/13/2003	DeYoung et al.		134	30	08/17/2001
	BB.H	6	5	6	4	8	2	6	05/20/2003	Shen		137	505.18	07/24/2001
	BB.I	6	5	7	6	1	3	8	06/10/2003	Sateria et al.		210	664	12/14/2000
	BB.J	6	5	8	3	0	6	7	06/24/2003	Chang et al.		438	723	07/03/2001
	BB.K	6	6	2	3	3	5	5	09/23/2003	McClain et al.		457	60	03/23/2001

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